



Colloquium

Extreme Ultraviolet:

Light up the Bright Future of the World

TSMC 奈米製像技術發展處 (NPTD)

先進曝光設備技術部 AETT

吳雪鴻 部經理 蘇彥碩 技術副理(102級系友)

極紫外光微影部EUVL 張俊霖 技術副理

Date: 2024/10/08(Tue)

Venue: S4-625

Time: 14:00-16:00

Abstract

1. The importance of lithography technology in semiconductor industry
2. What are the challenges of lithography process to extend Moore's Law
3. The complexity and knowledge required for EUV lithography
4. What did TSMC achieve to make EUV worldwide 1st production
5. What talent do we need to keep the leading position of Taiwan's semiconductor industry